

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (original): A polishing slurry comprising an abrasive comprising as a basic ingredient rare earth oxides containing cerium oxide, said polishing slurry further comprising an anionic surfactant and a nonionic surfactant and having a pH value of at least 11.

2. (original): The polishing slurry according to claim 1, wherein the abrasive comprises at least 90% by mass, based on the abrasive, of the rare earth oxides.

3. (original): The polishing slurry according to claim 1, wherein the rare earth oxides contain 50% to 90% by mass, based on the rare earth oxides, of cerium oxide.

4. (currently amended): The polishing slurry according to ~~any one of claims 1 to 3~~claim 1, wherein the rare earth oxides are produced from rare earth carbonate as a starting raw material.

5. (currently amended): The polishing slurry according to ~~any one of claims 1 to 4~~claim 1, wherein the abrasive is comprised of particles having a 50% cumulative average diameter (D50) in the range of 0.01 μm to 10 μm .

6. (currently amended): The polishing slurry according to ~~any one of claims 1 to 5~~claim 1, wherein the abrasive is comprised of particles having a specific surface area in the range of 1 m^2/g to 50 m^2/g .

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7. (currently amended): The polishing slurry according to ~~any one of claims 1 to 6~~claim 1, wherein the anionic surfactant is at least one ~~kind of~~ surfactant selected from the group consisting of low-molecular-weight compounds and high-molecular-weight compounds, which are selected from carboxylic acid salts, sulfonic acid salts, sulfuric acid ester salts and phosphoric acid ester salts.

8. (currently amended): The polishing slurry according to ~~any one of claims 1 to 7~~claim 1, wherein the nonionic surfactant is at least one ~~kind of~~ surfactant selected from the group consisting of polyoxyethylene alkyl phenyl ethers, polyoxyalkylene alkyl ethers and polyoxyethylene fatty acid esters.

9. (currently amended): The polishing slurry according to ~~any one of claims 1 to 8~~claim 1, which further comprises at least one ~~kind of~~ liquid medium selected from the group consisting of water, monohydric alcohols having 1 to 10 carbon atoms, glycols, polyhydric alcohols having 1 to 10 carbon atoms, dimethyl sulfoxide, dimethylformamide, tetrahydrofuran and dioxane.

10. (currently amended): The polishing slurry according to ~~any one of claims 1 to 9~~claim 1, which further comprises at least one ~~kind of~~ ingredient selected from the group consisting of phosphoric acid esters, cellulose ethers and water-soluble high-molecular-weight compounds.

11. (currently amended): A process for polishing a substrate, wherein ~~characterized in that~~ the polishing of the substrate is carried out by using the polishing slurry as claimed in ~~any one of claims 1 to 10~~claim 1.

12. (original): A process for producing a polished substrate comprising a step of polishing a substrate by the process as claimed in claim 11.

13. (original): A polished substrate obtainable by the process as claimed in claim 12.

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14. (original): The substrate according to claim 13, which is selected from the group consisting of a glass substrate for optical lens, a glass substrate for optical disc, a glass substrate for plasma display, a glass substrate for liquid crystal, a color filter for liquid crystal TV, a glass substrate for LSI photomask and a substrate for magnetic disc.